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## (54) RADIATION SENSITIVE RESIN COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a radiation sensitive resin composition excellent in shelf stability, having high transparency to radiation and excellent also in basic physical properties as a resist such as dry etching resistance, sensitivity, resolution and pattern shape.

SOLUTION: The radiation sensitive resin composition contains (A) an acid-dissociable group-containing resin having repeating units derived from a (meth) acrylic acid derivative having an alicyclic skeleton containing an oxygen- or nitrogen-containing polar group typified by 3-hydroxy-1-adamantyl (meth)acrylate or 3-(8'-cyanotetracyclo[4.4.0.12,5.17,10]dodecyl (meth)acrylate and repeating units derived from another (meth)acrylic acid derivative having an alicyclic skeleton typified by 2-methyl-2-adamantyl (meth)acrylate and convertible to an alkali-soluble resin when the acid-dissociable group is dissociated and (B) a radiation sensitive acid generating agent.

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